

ABSTRACT

5 A photomask blank including a transparent substrate, a film composed of a material containing chromium, and a film composed of a material containing tantalum is provided. The film composed of a material containing tantalum is constituted of a single layer or multiple layers, and has a thickness of 0.5 to 15 nm; the material containing tantalum contains tantalum, and oxygen or oxygen and nitrogen, and is free of silicon; the single
10 layer and at least the layer remotest from the transparent substrate among the layers constituting the multiple layers are composed of a material containing tantalum that has a tantalum content of 40 to 80 at%, an oxygen content of 5 to 50 at%, and a nitrogen content of not more than 50 at%; and the layer remotest from the transparent substrate has a thickness of not less than 0.5 nm.

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[Figure 3]